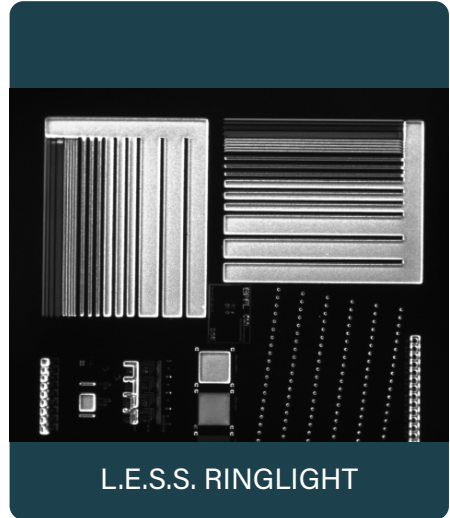
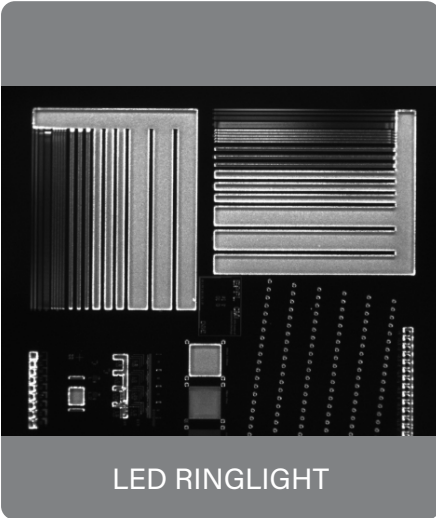


# APPLICATION NOTE



# INSPECTION OF A SILICIUM WAFER

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# ELIMINATION OF REFLEXIONS AND UNIFORM ILLUMINATION OF THE MICRO-STRUCTURES OF A SILICIUM WAFER



## PROBLEMATIC

Using standard LED illuminations to inspect a silicium wafer creates unwanted reflections on the surface of the sample that reduces the image quality.

## OUR SOLUTION

Using L.E.S.S. light, the user benefits from uniform illumination with neutral white light (5400°)

The light of the L.E.S.S. brightfield illumination hit the sample from the top with optimum intensity and no heat dissipation.



## APPLICATION

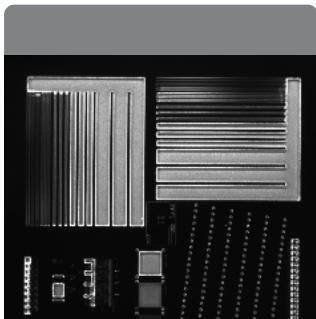
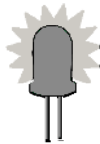
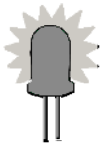
**Fig. 1** was taken with an entry-level LED ring at a working distance of 100 mm. Large shadow areas are present and unwanted reflections appear on the surface of the wafer. The different areas are not evenly illuminated such that some engravings are not observable.

**Fig. 2** was taken with a high-level ring of 80 LEDs in

the same configuration as **Fig. 1**. In this case, we can observe fewer reflections. However, some shadows remain and the engravings are only partially observable. **Fig. 3** was taken with L.E.S.S. ringlight (BF-5400) at a working distance of 100 mm.

The surface structure is entirely visible. No shadow areas are present on the mic

ro-structures such that all details are observed. The uniformity of the illumination results in sharp, well-defined images leading to a faster and more accurate and reliable inspection of the sample.



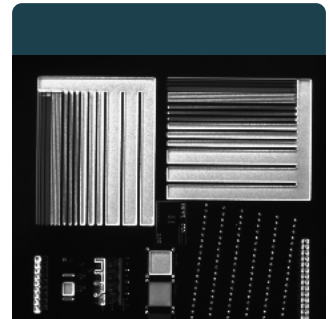
**Fig. 1**

Image of a wafer lit by an entry-level LED ringlight



**Fig. 2**

Image of a wafer lit by high-level 80 LEDs ringlight



**Fig. 3**

Image of a wafer lit by L.E.S.S. ringlight

RISK CLASS 0  
EN 62471 : 2006

EYE-SAFE  
CLASS 1 LASER PRODUCT  
ICE 60825-1 2014-05



**L.E.S.S. SA**

Av. de Longemalle 13  
CH-1020 Renens, Switzerland

Tel : +41 21 552 07 10

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⊕ BE BRILLIANT